Research and Development of Silicon Solar Cells in SANYO

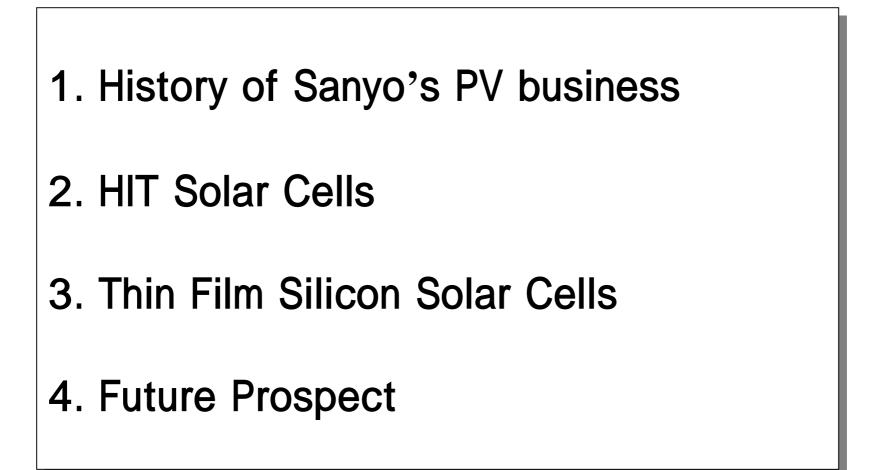
October 20, 2010

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SOLAR ARK

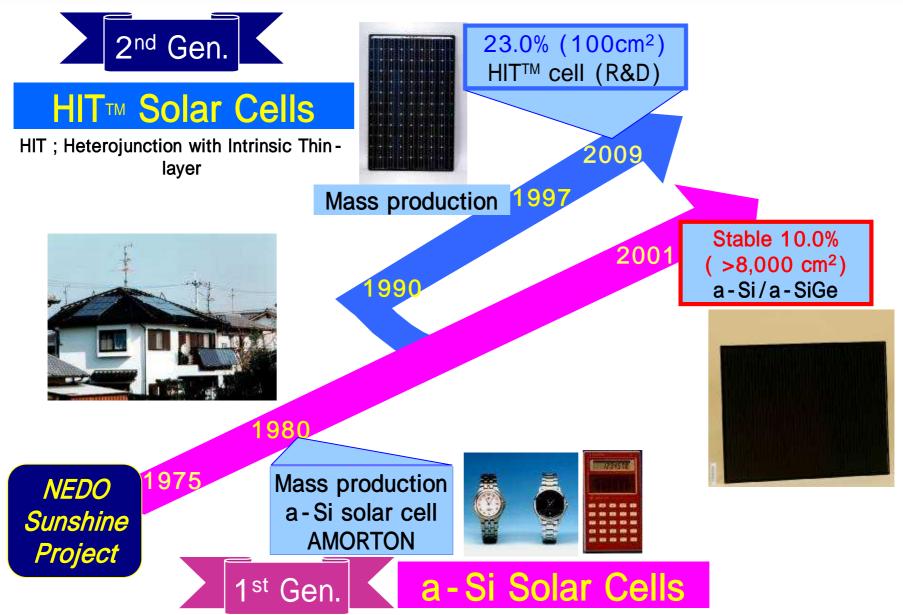
Makoto TANAKA Solar Energy Research Center SANYO Electric Co., Ltd.





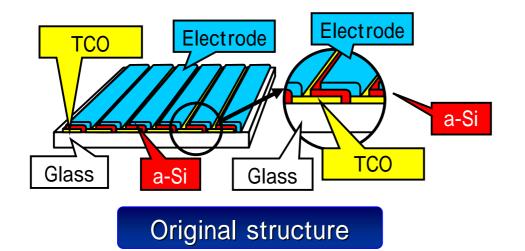
History of photovoltaic technology in SANYO





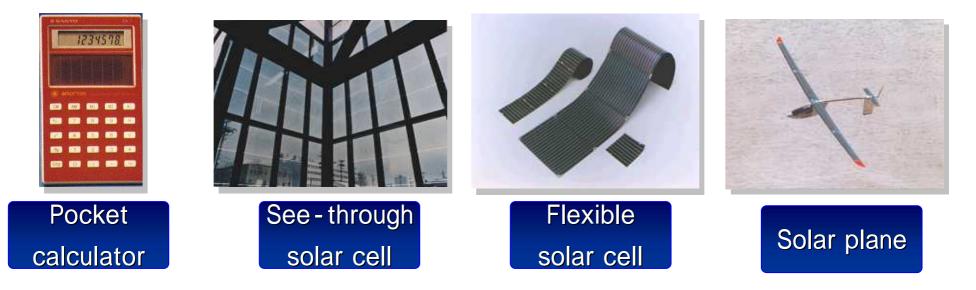
1st Generation in SANYO - Amorton -



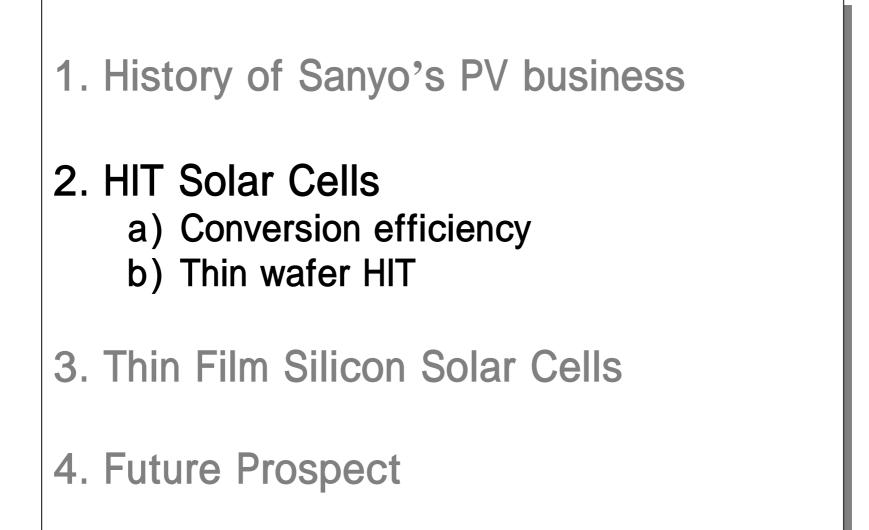




Residential use







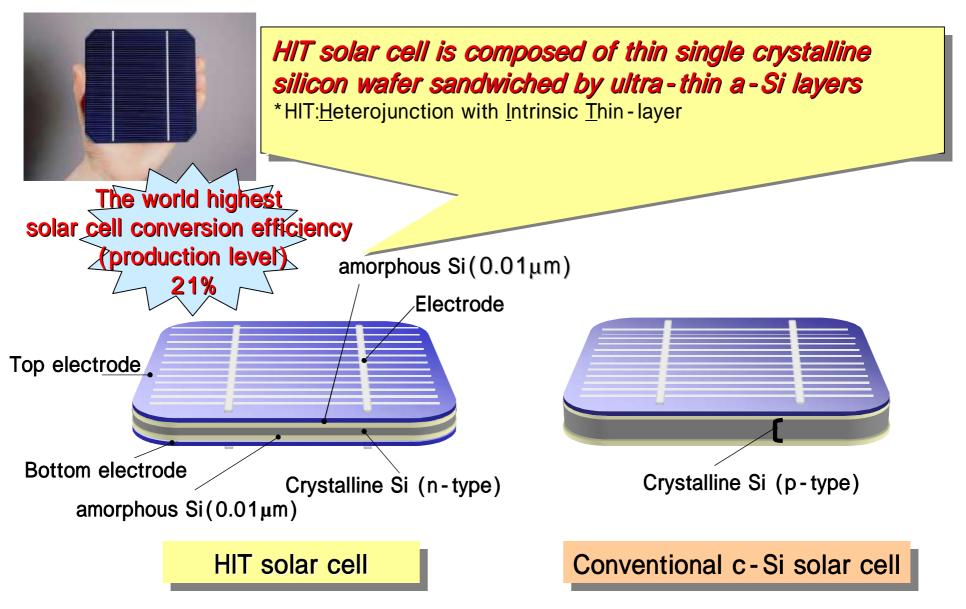
SANYO's Approaches to the PV Business



- 1. SANYO carries on a PV business by HIT solar cell, which is superior to solar cells of other companies.
- 2. All process including production of wafer, system and house building can be done in SANYO Group companies.
- 3. New technologies have been continuously created through research and development by members of world highest and maximum level.

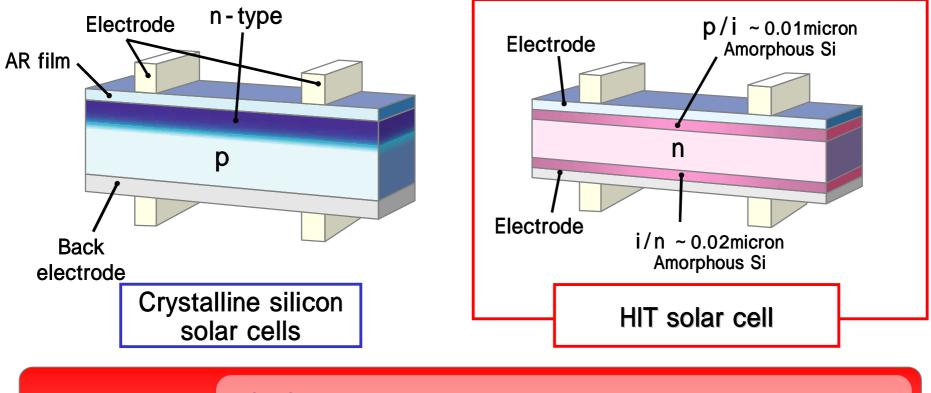
Structure of HIT Solar Cell



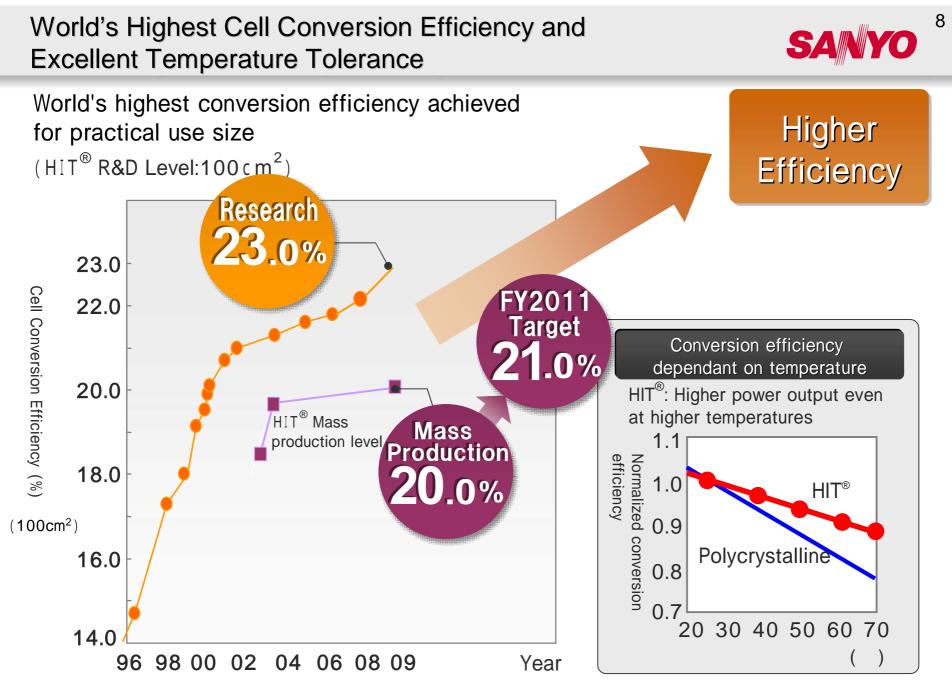




Synergy of crystalline and amorphous technologies

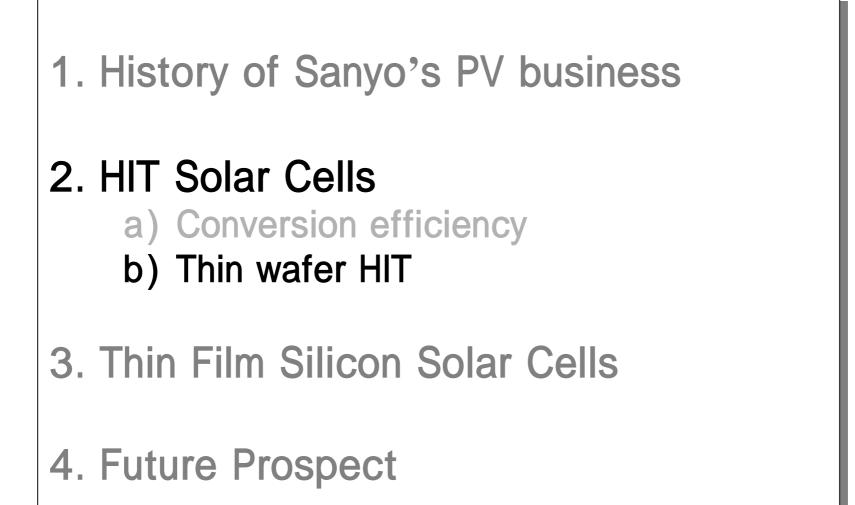


(1) Highest conversion efficiency
 (2) High performance even in Summer
 (3) Thin crystalline silicon



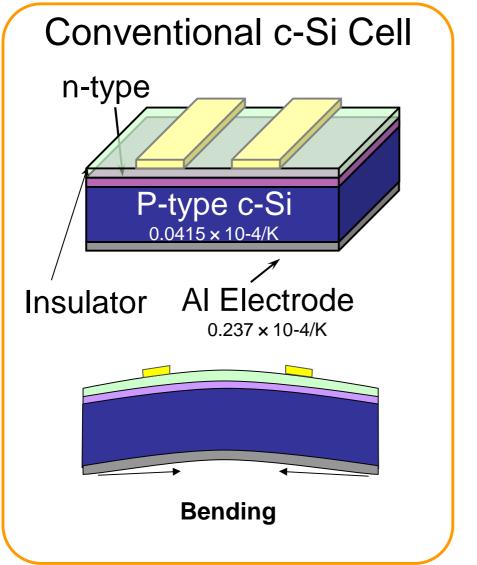
* HIT[®] is a registered trademark and an original technology of SANYO Electric Co., Ltd. Copyright(C) SANYO Electric Co., Ltd. 2010

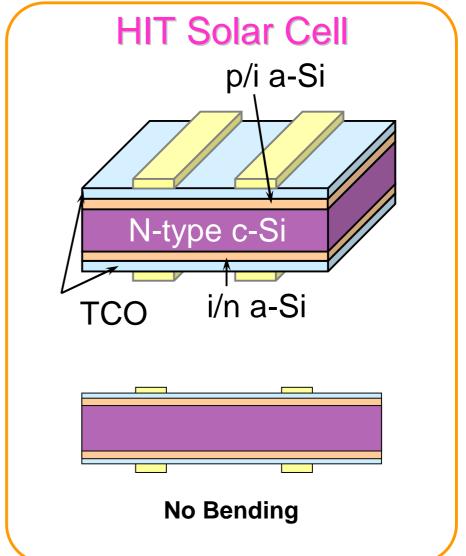




HIT Solar Cell has Advantage for Thinner Cell







Manufacturing Base

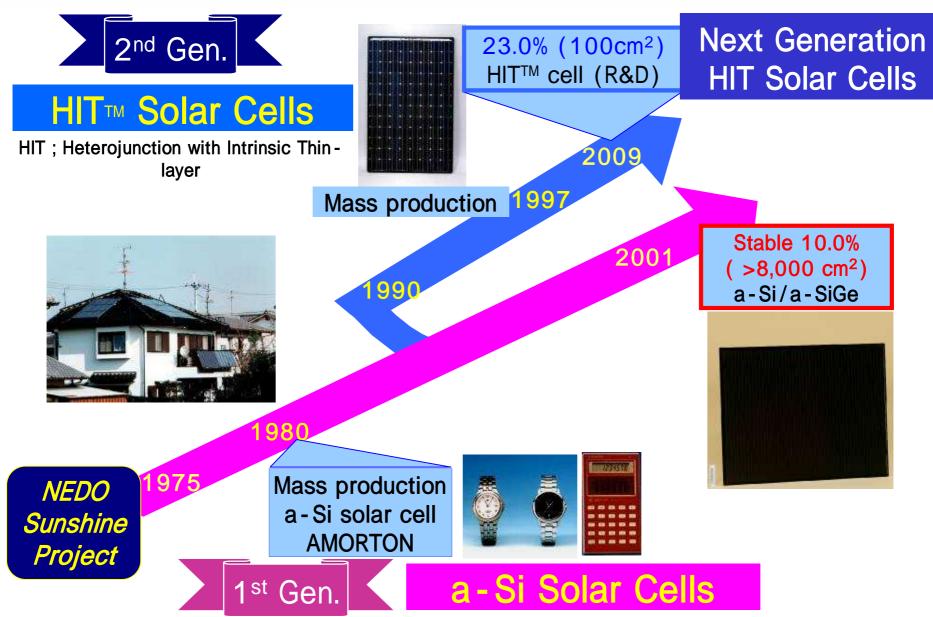


Expand Production in view of Mega Japan - Europe - U.S. Market



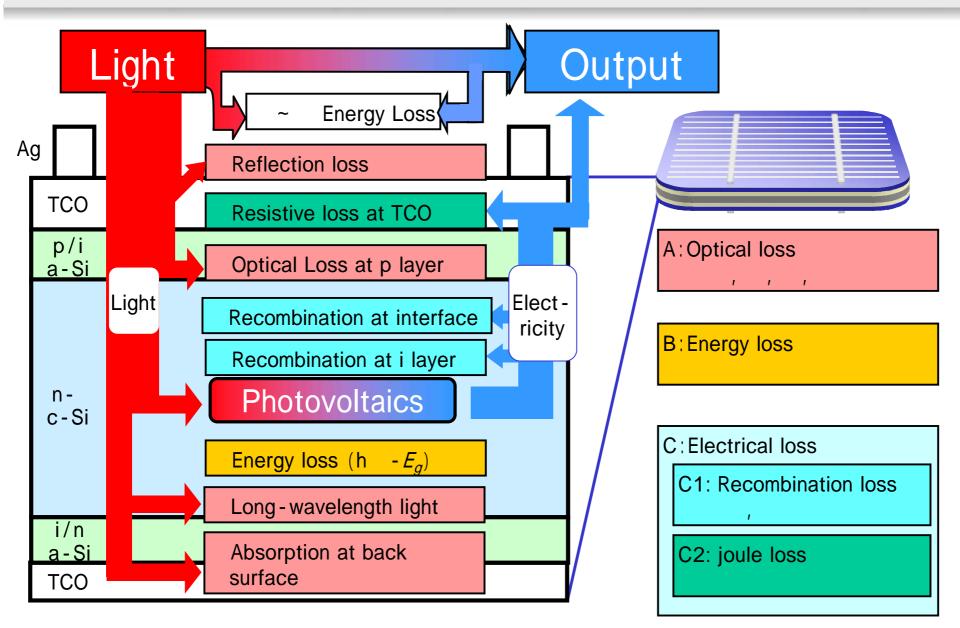
History of photovoltaic technology in SANYO





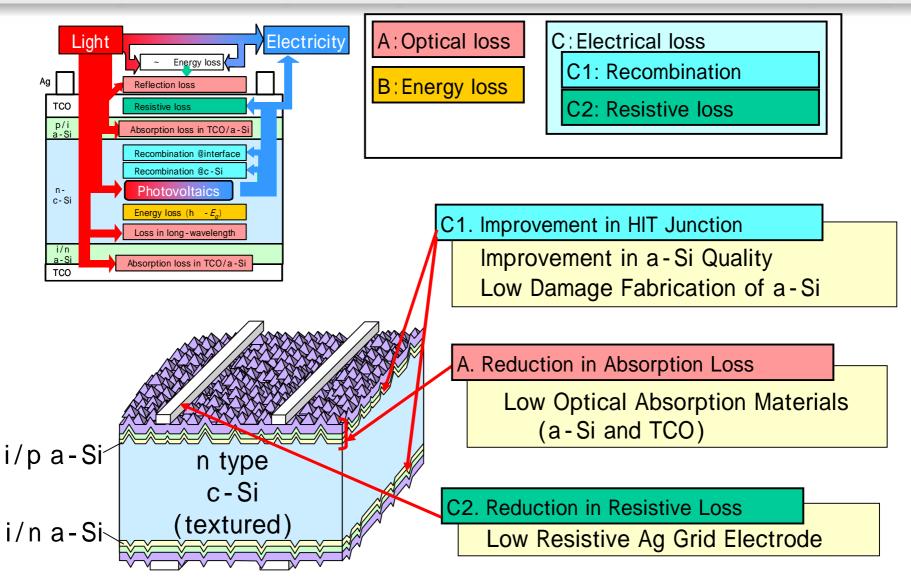
Loss in HIT Solar Cell

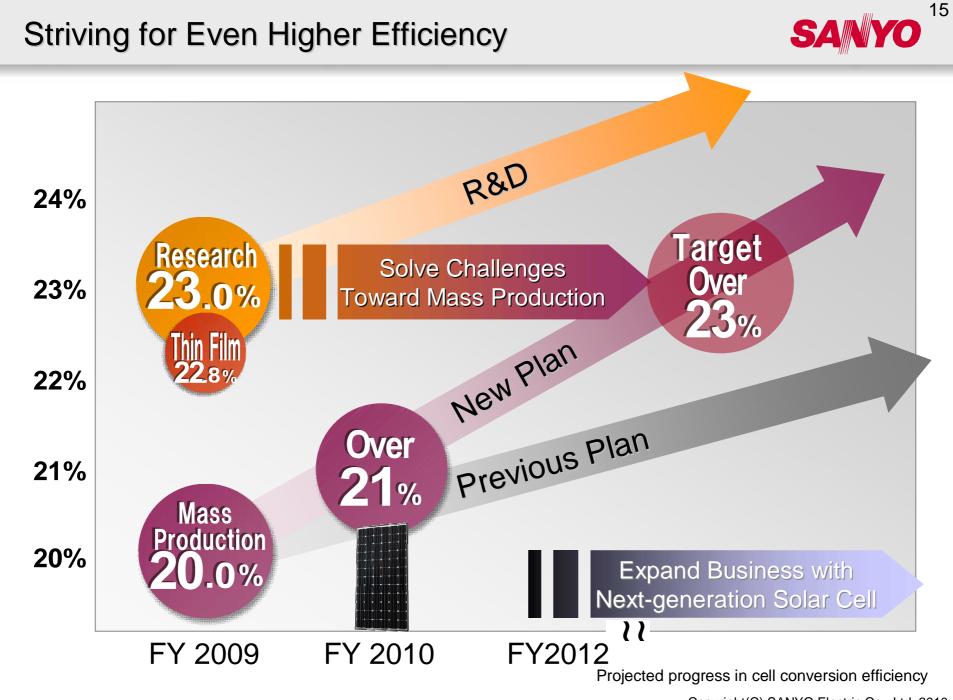




Key Technologies for High Efficiency



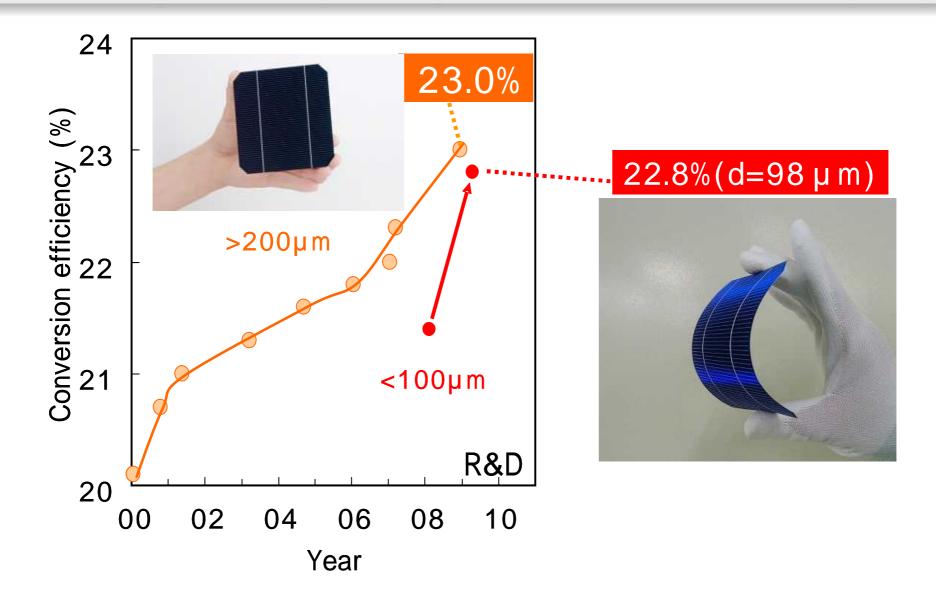




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16 SAN Next Generation Solar Cell **Development Concept** Design that reduces the efficiency loss to nearly the theoretical limits Conversion Efficiency: Over 23% Period: Commercialization starting in FY 2014 (Accelerate schedule as soon as possible) Structure: HIT[®] structure Technology: Applying the performance of thin substrate technology Thickness: Thinner than current HIT[®] Cost: Lower costs Location: Currently under investigation with Panasonic s Amagasaki plant as the primary candidate

Progress of Conversion Efficiency in HIT Solar Cell SANYO



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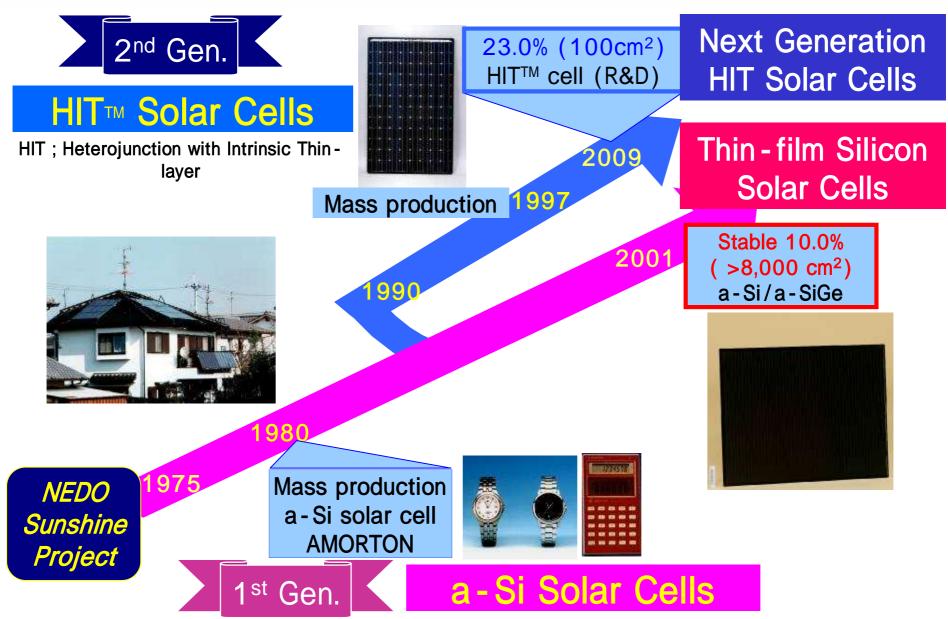




- 2. HIT Solar Cells
- 3. Thin Film Silicon Solar Cells
 a) New Research Center
 b) New p-CVD
- 4. Future Prospect

History of photovoltaic technology in SANYO





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G 5.5 Glass Substrate for Mass Production



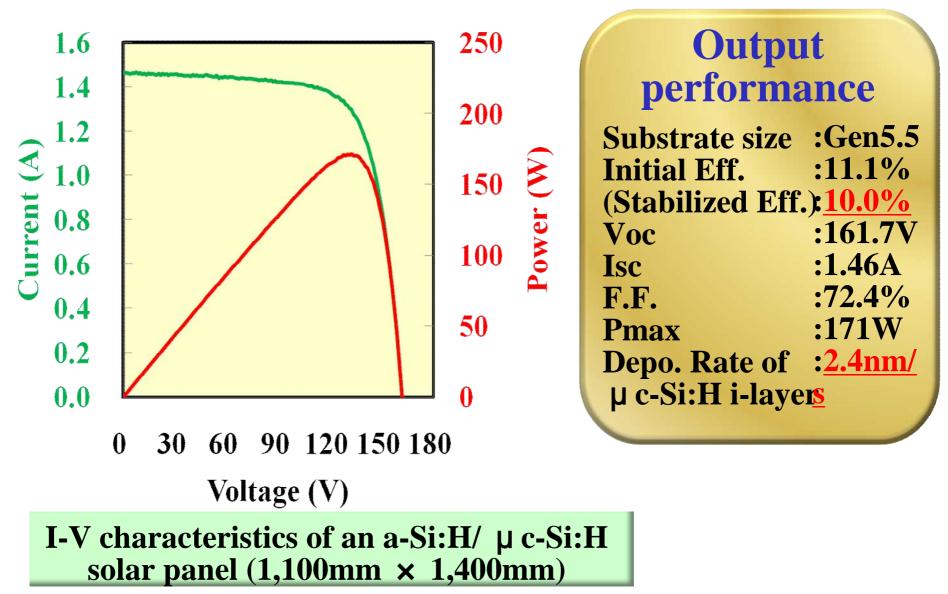


Tandem Panel

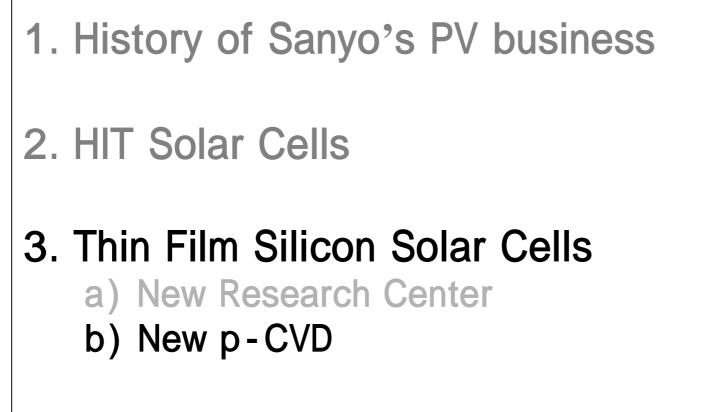
Tandem module (InterSolar 2008, Munich) Copyright(C) SANYO Electric Co., Ltd. 2010

Output performance of Gen5.5 module





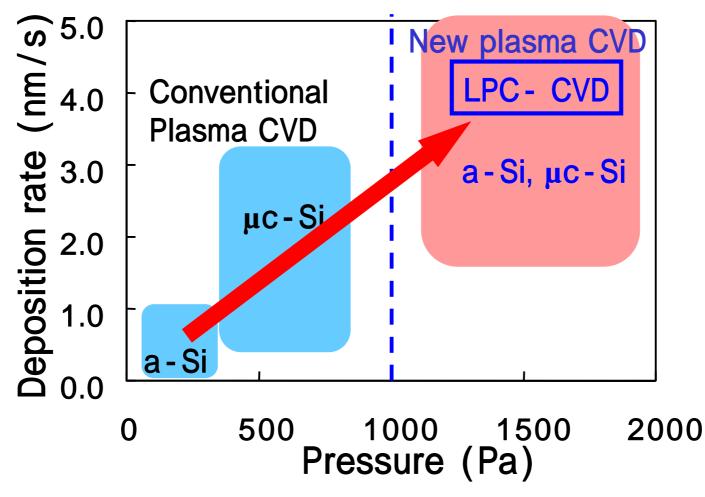




4. Future Prospect



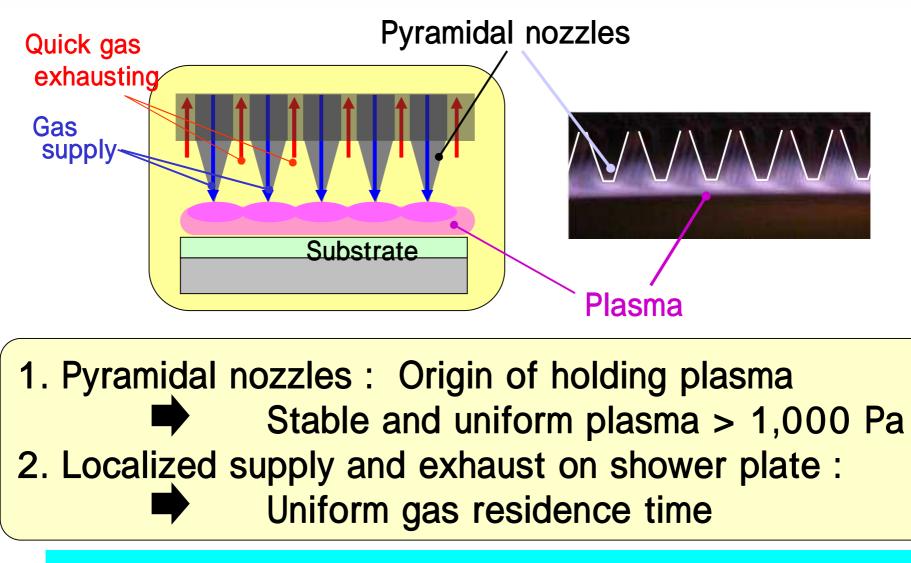
High Pressure Plasma is Necessary for High Rate Deposition



LPC : Localized Plasma Confinement

New plasma CVD 'LPC - CVD'

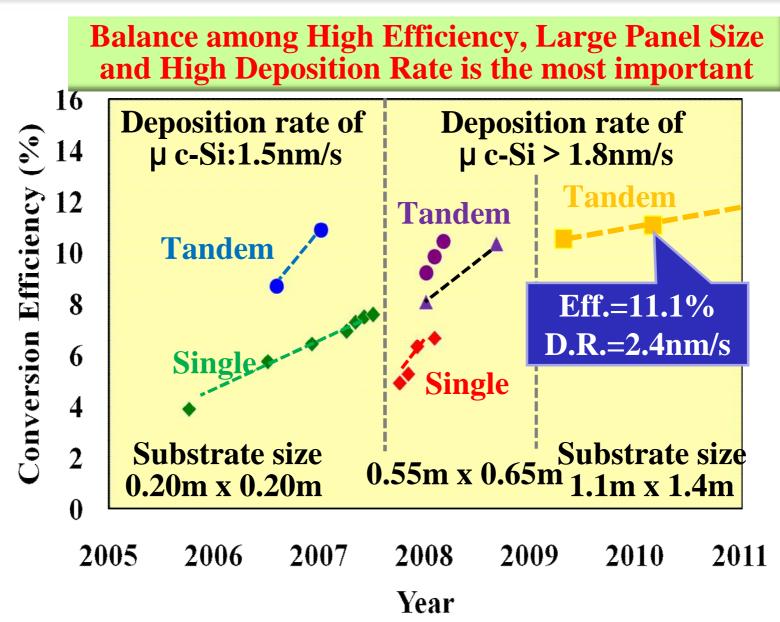




High rate and uniform deposition on large substrates

Progress in the Performance





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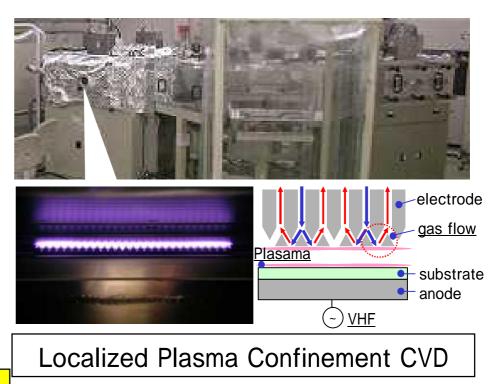
New original technologies under development



Original technologies have been under development. ex) Very high thoughput deposition technology, Localised Plasma Confinment (LPC) CVD method

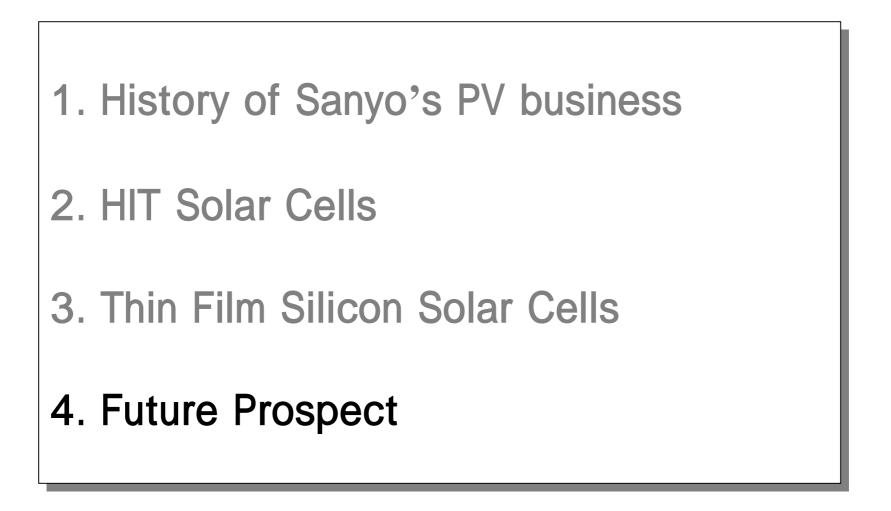
Original technologies have been developed in NEDO R&D

- 1. Higher throughput (10 times higher) "Localized Plasma"
- 2. Higher performance from 10% to >14% (same level with multi-Si) Technology of new thin Si



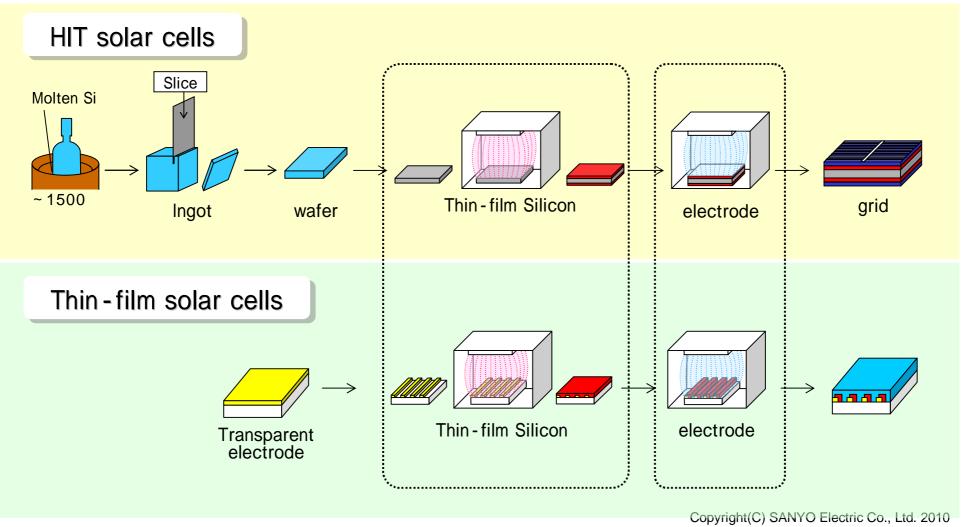
Accelerate in "Advanced Photovoltaics Development Center"



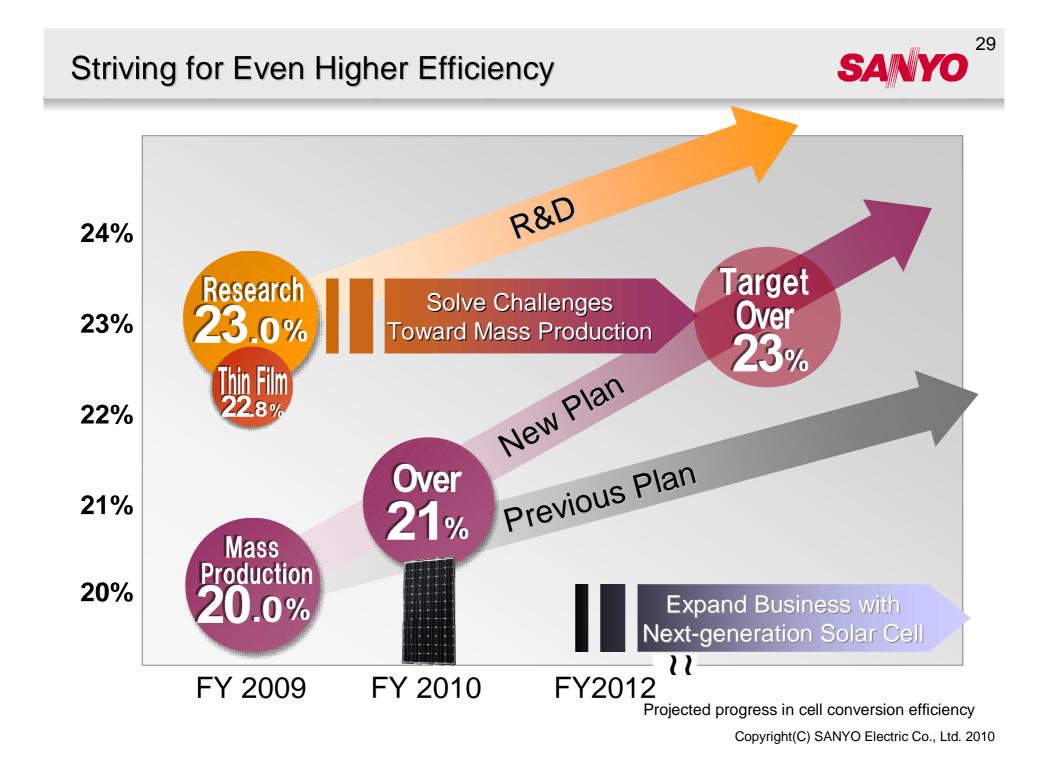


Fusion ; technologies of HIT and Thin-film Solar Cells **SANYO**

Technologies for thin-film Si solar cells are similar to those of HITsolar cells. Therefore, the highest level technologies for HIT can be easilyapplied to thin-film Si solar cells.

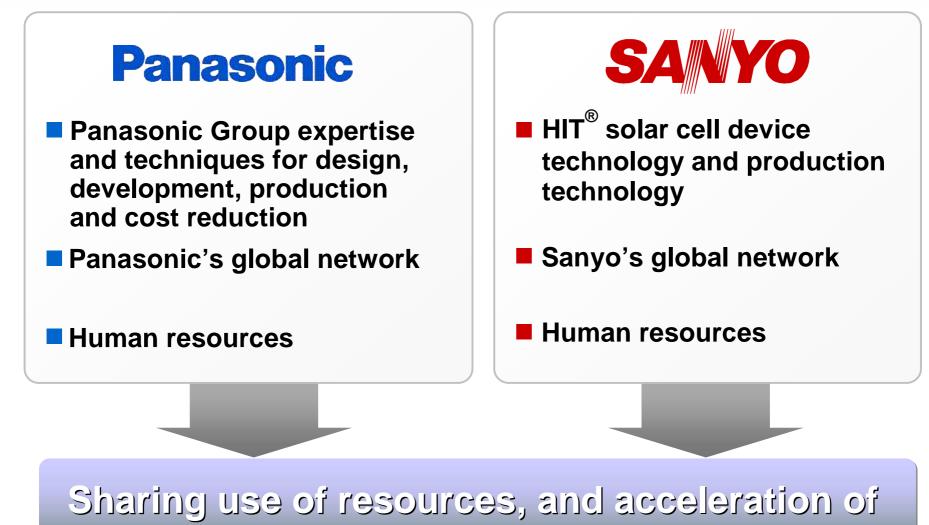


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Sharing the Use of Assets to Become one of the Global Top 3





efforts to become one of the global top 3 by 2015



